

AMENDMENTS TO THE SPECIFICATION

1. Please substitute context of Paragraph [0019] of the specification with the following amended context:

5

“As shown in Fig.5, a title angle ion bombardment process is then carried out at an incident title angle of about ~~3°-7°~~ 3 to 7 degrees relative to the axis (not shown) that is perpendicular to the main surface 11 of the semiconductor substrate 10.”

10